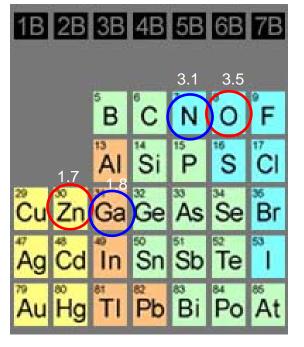
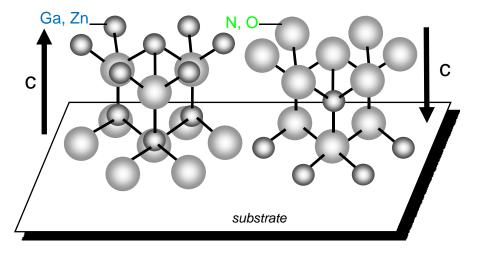


GaN, ZnO crystal structure





GaN: a=3.185 A, c=5.185 A c/a=1.625 ZnO: a=3.250 A, c=5.207 A c/a=1.602 (0001) Ga, Zn-face (+c polarity) (0001) N, O-face (-c polarity)

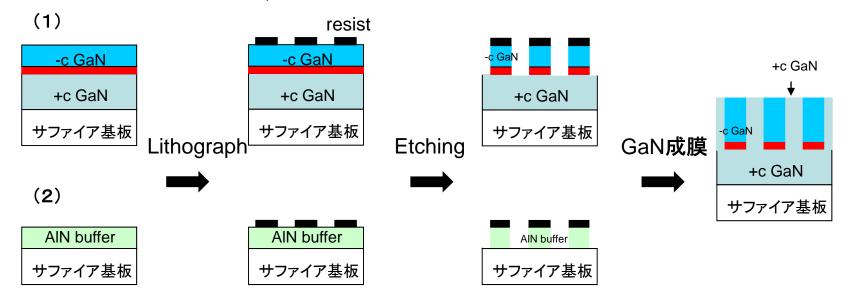


•Growth along c-axis \rightarrow Film growth

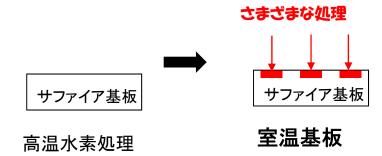
•Spontaneous polarization \rightarrow device performance

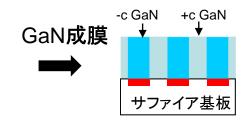
面内極性制御プロセス

従来のプロセス(製膜方法:MBE)



本プロセス(MOCVD)



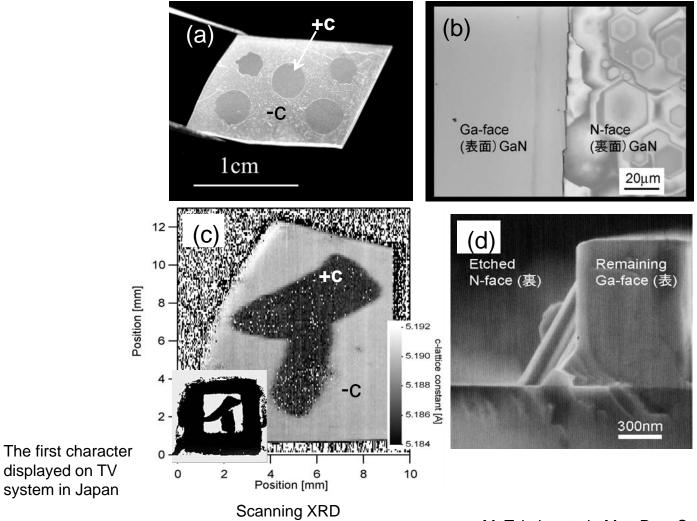




In-plane control of polarity



Dipping a sapphire substrate annealed at 1080°C in H₂ ambient into HNO₃ solusion



M. Takabe et al., Mat. Res. Soc. Symp. 798, 305 (2004).